



EVG[®]120

Automated Resist Processing System



Introduction

The EVG[®]120 is a compact, cost-effective resist processing system for starting up production when cleanroom space is limited.

The new EVG120 universal and fully automated resist processing tool is capable of processing various substrate shapes and sizes up to 200 mm/8". This new generation of the EVG120 comes in a new ultra-compact design with newly developed chemistry cabinet for external storage of chemicals while providing increased throughput capability, optimized for high-volume customer needs and ready for utilization in high volume manufacturing (HVM). The EVG120 provides users with an elaborate set of benefits that is simply not found in any other tool and guarantees the highest quality standards in various fields of application at a remarkably low cost of ownership.

Technical Data	
Wafer diameter (substrate size)	up to 200 mm
Available modules	- Spin coat / OmniSpray [®] / develop - Bake / chill
Wafer handling options	- Single/double EE / edge handling / wafer flipping - Bowed / warped / thin wafer handling
Dispense options	- various resist dispense pumps to cover a wide range of viscosities up to 52000 cP - constant pressure dispense systems - EBR / BSR / pre-wet / bowl wash / liquid priming

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Features

- Wafer sizes up to 200 mm
- Ultra-compact design for minimal footprint
- Up to 2 coat/develop chambers and 10 hot/chill plates
- Possible combinations of multi-functional modules for spin and spray coating, developing, bake and chill
- Chemistry cabinet for external storage of chemicals
- OmniSpray[®] ultrasonic atomization technology for conformal coating of extreme topographies
- CoverSpin[™] cover for low resist consumption and optimized resist coating uniformity
- Megasonic technology for cleaning, sono-chemical processing and developing improves process efficiency and lowers the process time from hours to minutes
- Process technology excellence and development service
- Multi-user concept (unlimited number of user accounts and recipes, assignable access rights, different user interface languages)
- Smart process control and data analysis features
 - equipment and process performance tracking and data analysis features
 - parallel/ queueing task processing feature
 - smart handling features
 - occurrence and alarm analysis features
 - smart maintenance and tracking features

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